

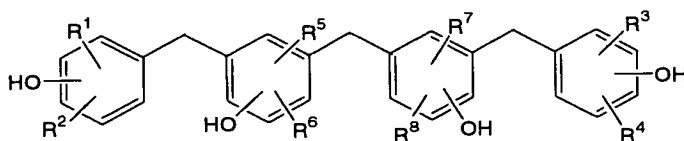
WHAT IS CLAIMED IS:

1. A positive photoresist composition comprising:

(A) an alkali-soluble resin;

(B) a photosensitizer comprising a quinonediazide ester between a naphthoquinonediazidosulfonic acid compound and at least one of a compound represented by following Formula

(I):



(I)

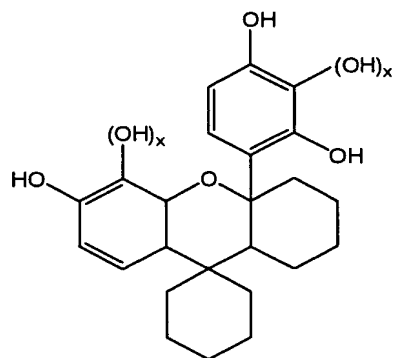
wherein  $R^1$ ,  $R^2$ ,  $R^3$ ,  $R^4$ ,  $R^5$ ,  $R^6$ ,  $R^7$  and  $R^8$  are each independently a hydrogen atom or an alkyl group having from 1 to 3 carbon atoms, and a compound represented by following Formula (II):



(II)

wherein  $R^9$ ,  $R^{10}$ ,  $R^{11}$ ,  $R^{12}$ ,  $R^{13}$ ,  $R^{14}$ ,  $R^{15}$ ,  $R^{16}$ ,  $R^{17}$  and  $R^{18}$  are each independently a hydrogen atom, an alkyl group having from 1 to 3 carbon atoms or a cyclohexyl group; and

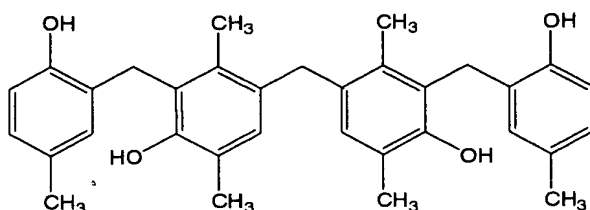
(C) a sensitizer comprising at least one of compounds represented by following Formula (III):



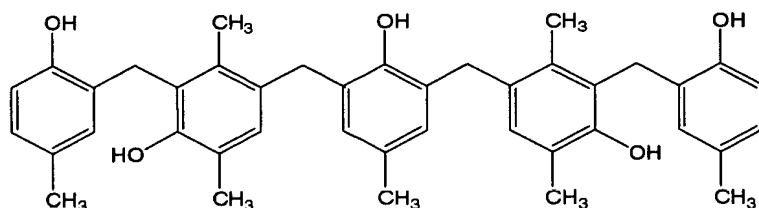
(III)

wherein  $x$  is 0 or 1.

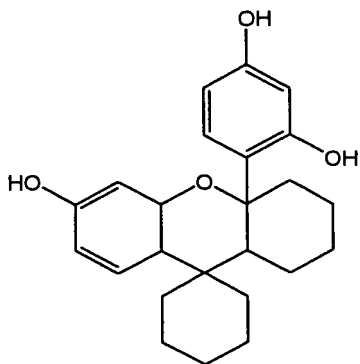
2. The positive photoresist composition according to claim 1, wherein the compound represented by Formula (I) is a compound represented by the following formula:



3. The positive photoresist composition according to claim 1, wherein the compound represented by Formula (II) is a compound represented by the following formula:



4. The positive photoresist composition according to claim 1, wherein the compound represented by Formula (III) is a compound represented by the following formula:



5. The positive photoresist composition according to claim 1, wherein the compound represented by Formula (III) is a compound represented by the following formula:

